

Search Notes 	Application/Control No.	Applicant(s)/Patent under Reexamination
	10/817,567	LIN ET AL.
	Examiner	Art Unit
	D. Rutledge	2851

SEARCH NOTES (INCLUDING SEARCH STRATEGY)		
	DATE	EXMR
develop\$3 near3 (wafer or substrate); rotat\$3 near3 (wafer or substrate); (wash\$3 or rins\$3) near4 (substrate or wafer)	3/19/2005	DR
(front or upper or top or patterned) near2 (surface or side); (back or rear or reverse) near2 (side or surface); (stop\$4 or	3/19/2005	DR
terminat\$3 or end\$3 or discontinu\$4) near3 (wash\$3 or rins\$3) near4 (rear or back or reverse)	3/19/2005	DR

INTERFERENCE SEARCHED			
Class	Subclass	Date	Examiner
396	604,611	3/19/2005	DR
396	626	3/19/2005	DR
118	52,319	3/19/2005	DR
134	32, 157	3/19/2005	DR